SUBSTRATE PROCESSING METHOD AND SUBSTRATE PROCESSING APPARATUS

ABSTRACT

A substrate processing method for processing a substrate by supplying a gas from a gas supply part to a substrate processing space in a substrate processing apparatus, wherein the gas supply part includes a plurality of gas sources, a flow path that allows the gas to flow from the plurality of gas sources to the substrate processing space, a valve provided in the flow path to switch between opening and closing the flow of the gas, and a buffer tank provided in the flow path, pulse control is performed to pulse the flow of the gas by alternately repeating the opening and closing of the flow of the gas in the valve, and in the pulse control, a duration of the pulse control and a number of times of opening the flow of the gas during the duration are controlled to control the flow rate of the gas.

Fig. 7